

2. (Amended) The reticle sorter of claim 1, further including a controller coupled to the sorting system for controlling the sorting of the reticles [according] in response to a command from a host system.

B1 3. (Amended) The reticle sorter of claim 1, further including a storage location for holding a reticle, wherein the sorting system may place a selected reticle on the storage location during a sorting operation.

8. (Amended) The reticle sorter of claim 5, wherein the inspection system includes a tool adapted for [detection] detecting flaws in a reticle pattern.

9. (Amended) The reticle sorter of claim 5, further including means for moving each of the cassettes from the input port to one of the one or more bays.

11. (Amended) The reticle sorter of claim 10, wherein the sorting system [can] is adapted to move reticles between a first cassette in a first one of the two or more docking locations and a second cassette in a second one of the two or more docking locations.

B2 13. (New) A reticle sorter coupled between a reticle storing system and one or more photolithography exposure tools, comprising:

one or more bays adapted for holding a plurality of cassettes having slots for reticles; and
a sorting arrangement adapted for retrieving the reticles from and inserting the reticles into the slots so as to sort the reticles between cassettes.

Remarks

The Office Action dated November 20, 2000, indicated that claims 1-12 stand rejected under §112, first paragraph as not being enabled by the specification and that claim 1 stands rejected under §112, second paragraph as being indefinite with the scope of the claim being unascertainable. In addition, claims 1, 3, 5, 7 and 9-12 stand rejected under §103(a) as being unpatentable over *Iizuka* (U.S. Patent No. 4,999,671) in view of *Sussman et al.* (U.S. Patent No.